

OIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400
Facsimile: (703) 836-2787

PATENT APPLICATION

Attorney Docket No.: 107291

AMENDMENT TRANSMITTAL

In re the Application of

Shunichi SEKI et al.

Group Art Unit: 1762

Application No.: 09/701,534

Examiner: M. Cleveland

Filed: November 30, 2000

For: METHOD FOR FORMING SILICON FILM AND INK COMPOSITION FOR INK JET

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Transmitted herewith is an Amendment in the above-identified application.

- ☐ Entitlement to small entity status is hereby asserted.
☐ Small entity status of this application has been established.

The filing fee has been calculated as shown below:

	(Column 1)	(Column 2)	(Column 3)	SMALL ENTITY		OTHER THAN A SMALL ENTITY	
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NO. PREVIOUSLY PAID FOR	PRESENT EXTRA	RATE	ADD'L FEE	RATE	ADD'L FEE
TOTAL CLAIMS	*23	22	= 1	x 9	\$	x 18	\$ 18.00
INDEP CLAIMS	* 5	4	= 1	x 42	\$	x 84	\$ 84.00
<input type="checkbox"/> FIRST PRESENTATION OF MULTIPLE DEP. CLAIM				+ 140	\$	+ 280	\$
					\$		\$ 102.00

- * If the entry in Column 1 is less than the entry in Column 2, write "0" in Column 3.
** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.
*** If the "Highest Number Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.

The "Highest Number Previously Paid For" in this space (Total or Independent) is the highest number found from the equivalent box in Column 1 of a prior Amendment or the number of claims originally filed.

- ☒ Check No. 138354 in the amount of \$102.00 is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.

DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
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Respectfully submitted,

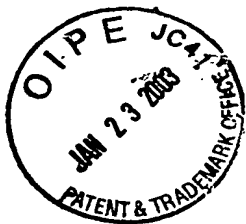
James A. Oliff
Registration No. 27,075

Jeffery M. Lillywhite
Registration No. P-53,220

JAO:JML/vgp

Date: January 23, 2003

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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Shunichi SEKI et al.

Application No.: 09/701,534

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For: METHOD FOR FORMING SILICON FILM AND INK COMPOSITION FOR INK JET

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the July 23, 2002 Office Action, the period for response being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1, 4, 13-15 and 22 as follows:

B¹
1. (Twice Amended) A method for forming a silicon film, comprising:
applying by patterning an ink composition containing a silicon compound onto a substrate by an ink jet process, the silicon compound having at least one cyclic structure.

B²
4. (Twice Amended) The method for forming a silicon film according to claim 3, further comprising:
a step for irradiating the silicon film formed by heat treatment and/or light treatment with laser to convert the amorphous silicon film into a polycrystalline silicon film.

B³
13. (Twice Amended) The method for forming a silicon film according claim 1, the composition being a viscosity of 1 to 50 mPa·s and a surface tension of 20 to 70 dyn/cm.

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02 FC:1201

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